



**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q77191

Koichi OHTO, et al.

Appln. No.: 10/650,193

Group Art Unit: 2826

Confirmation No.: 6245

Examiner: Alexander O. WILLIAMS

Filed: August 28, 2003

For: SEMICONDUCTOR DEVICE HAVING SILICON-DIFFUSED METAL WIRING  
LAYER AND ITS MANUFACTURING METHOD

**PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. § 1.136, Applicant hereby petitions for an extension of time of three month(s), extending the time for responding to the Office Action of May 20, 2005 to November 20, 2005.

A check for the statutory fee of \$1,020.00 is attached. The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

John K. Shin

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WASHINGTON OFFICE

**23373**

CUSTOMER NUMBER

Date: November 15, 2005

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